

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Ogata et al.
Appl. No.	:	10/589,681
Filed	:	August 16, 2006
For	:	POLYMER COMPOUND, PHOTORESIST COMPOSITION INCLUDING THE POLYMER COMPOUND, AND RESIST PATTERN FORMATION METHOD
Examiner	:	Chu, John S Y
Group Art Unit	:	1795

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **June 24, 2009**, please consider the following amendments and remarks:

Amendments to the Claims are reflected in the listing of claims begins on page 2 of this paper.

Remarks begin on page 8 of this paper.